

Session 8: Solid State Physics

MS Junction

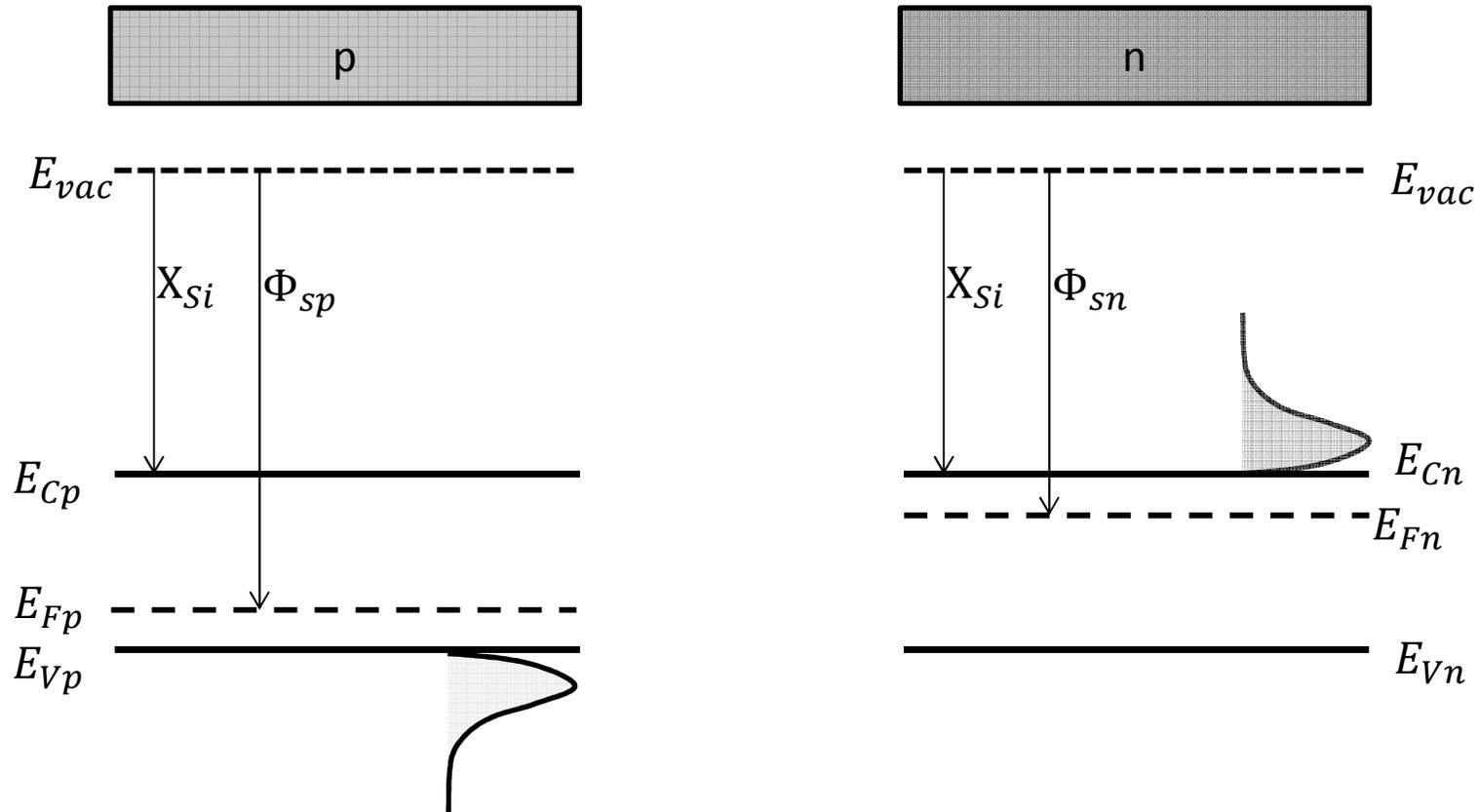
Outline

1.	██████████
2.	██████████████
3.	██████████
4.	██████
5.	██████

- ◎ A
 - B
 - C
 - D
 - E
- ◎ F
 - G
- ◎ H
- ◎ I
- ◎ J

PN junctions – Before Being Joined

1. 
2. 
3. 
4. 
5. 



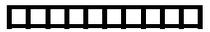
electrically neutral in every region

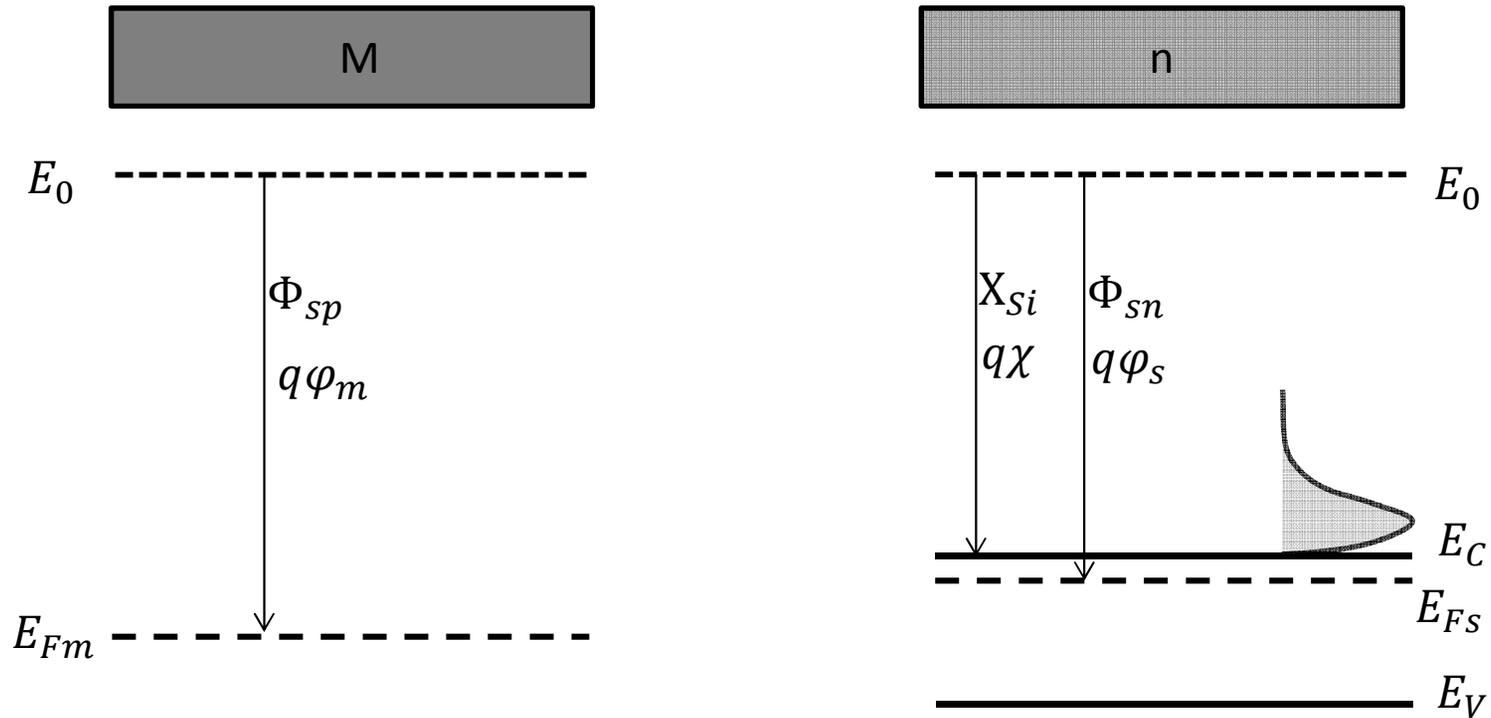
electron affinity : X_{Si}

work function Φ : $\Phi = E_{vac} - E_F$

$$\Phi_n \neq \Phi_p$$

MS junctions – Before Being Joined

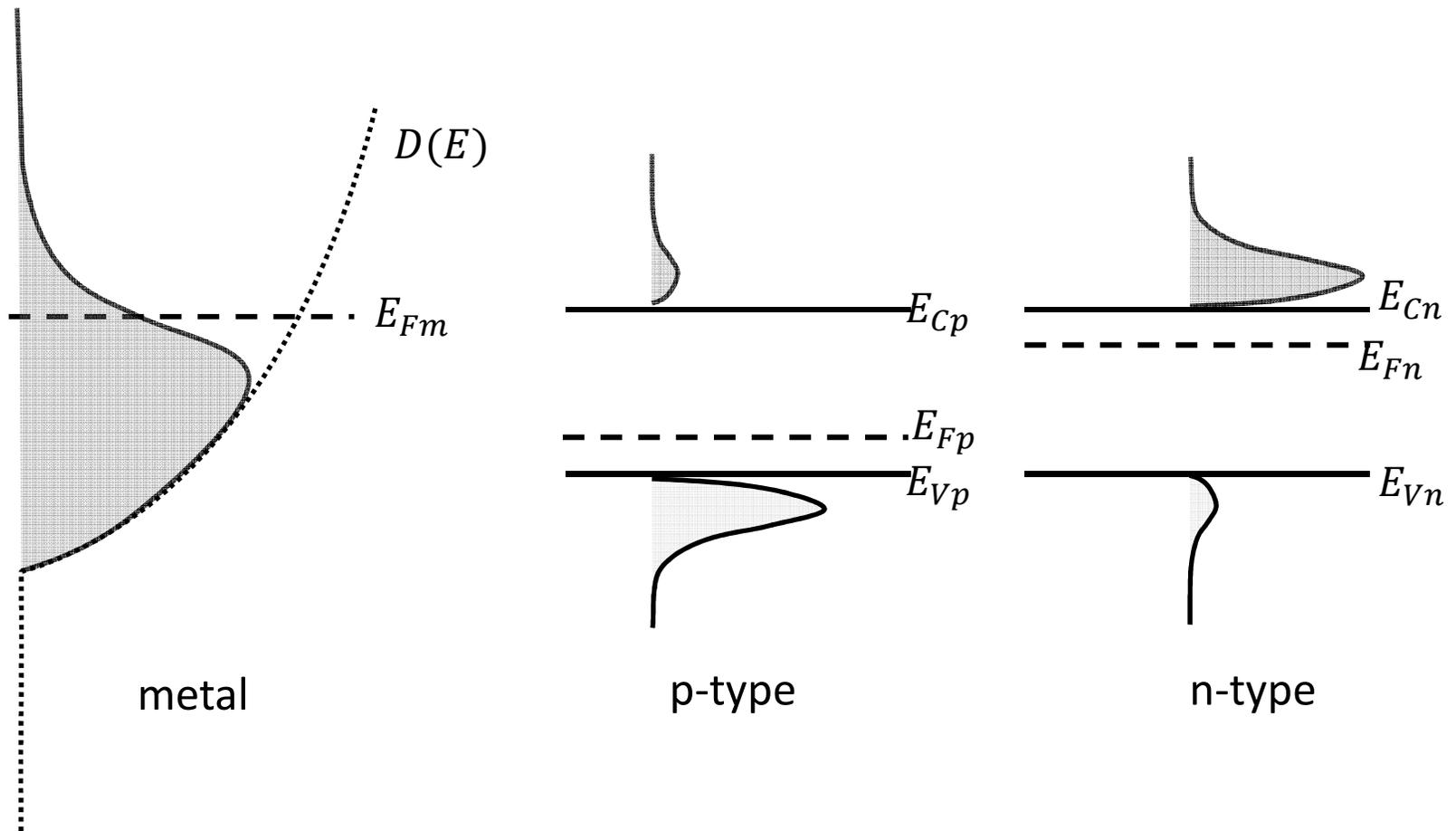
1. 
2. 
3. 
4. 
5. 



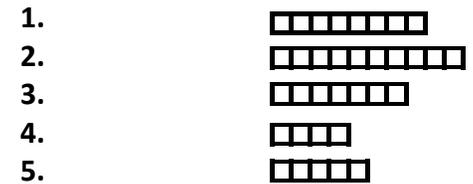
$q\phi_m$ work function $\phi_{Au} = 4.75eV$, $\phi_{Cu} = 4.5eV$, $\phi_{Al} = 4.28eV$
 $q\chi$ electron affinity $\chi_{Si} = 4.05eV$, $\chi_{Ge} = 4eV$, $\phi_{GaAs} = 4.07eV$

Reminder

1. 
2. 
3. 
4. 
5. 



Plotting Energy Bands for MS Junction

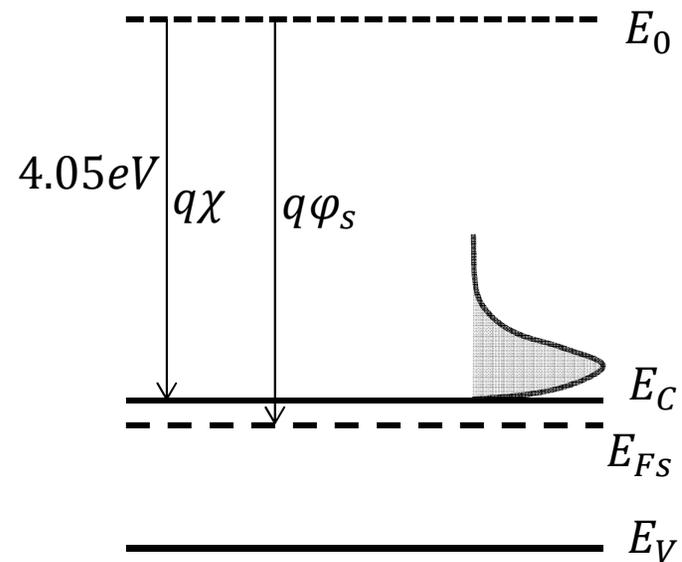
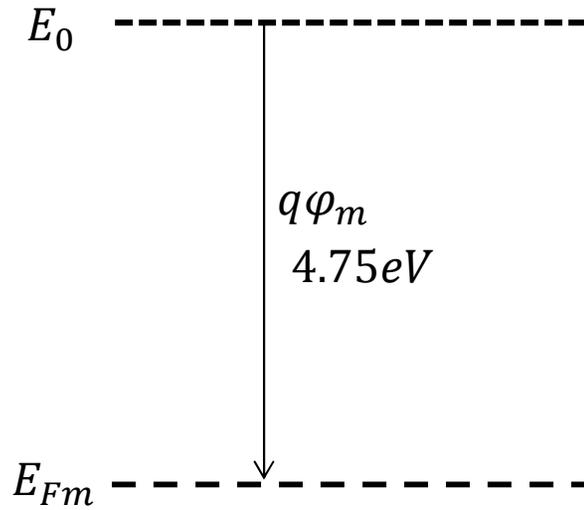
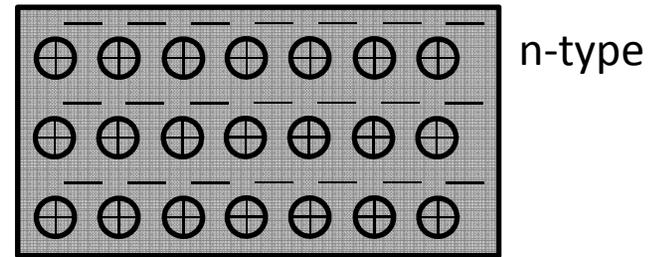


Step by step:

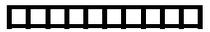
1. Vacuum energy (E_0) is continuous.
2. E_G and χ are intrinsic properties of materials and should remain constant. (which means E_C , E_V , and E_0 are all parallel)
3. At equilibrium E_F is constant while by applying voltage $\Delta E_F = -qV$.

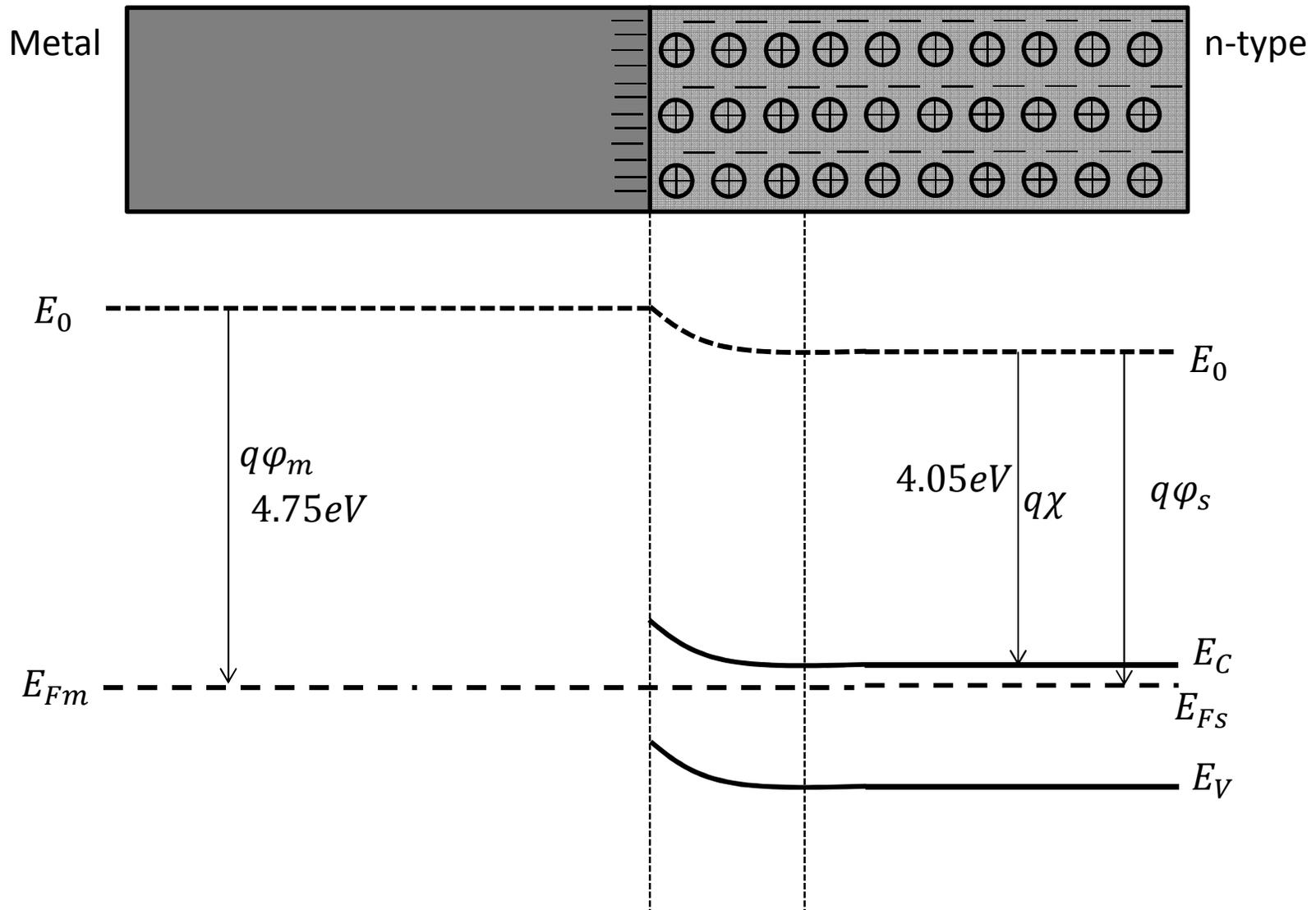
MS junctions – Before Being Joined

1. 
2. 
3. 
4. 
5. 

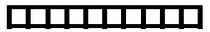


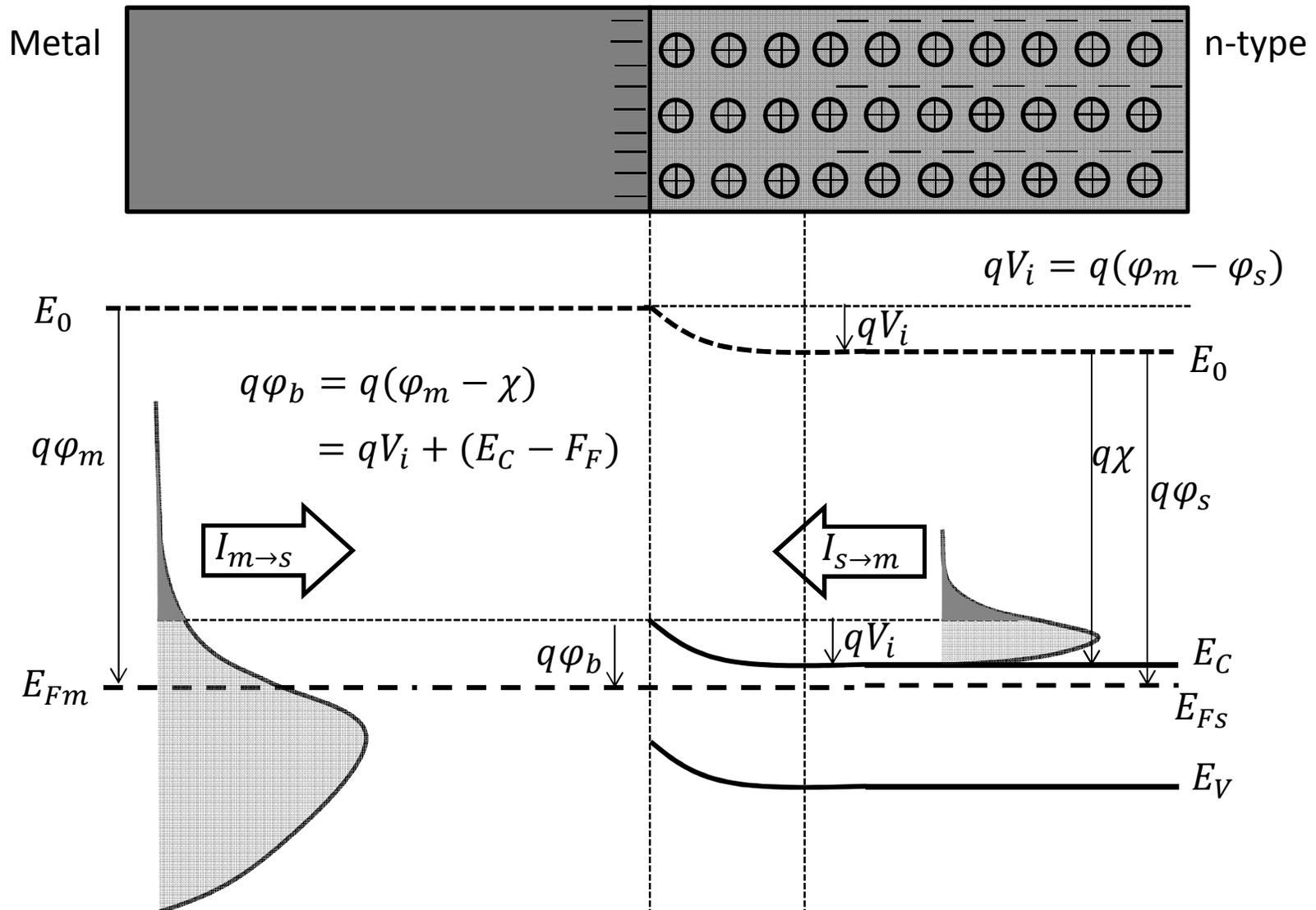
MS junctions – Qualitative

1. 
2. 
3. 
4. 
5. 

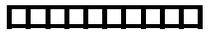


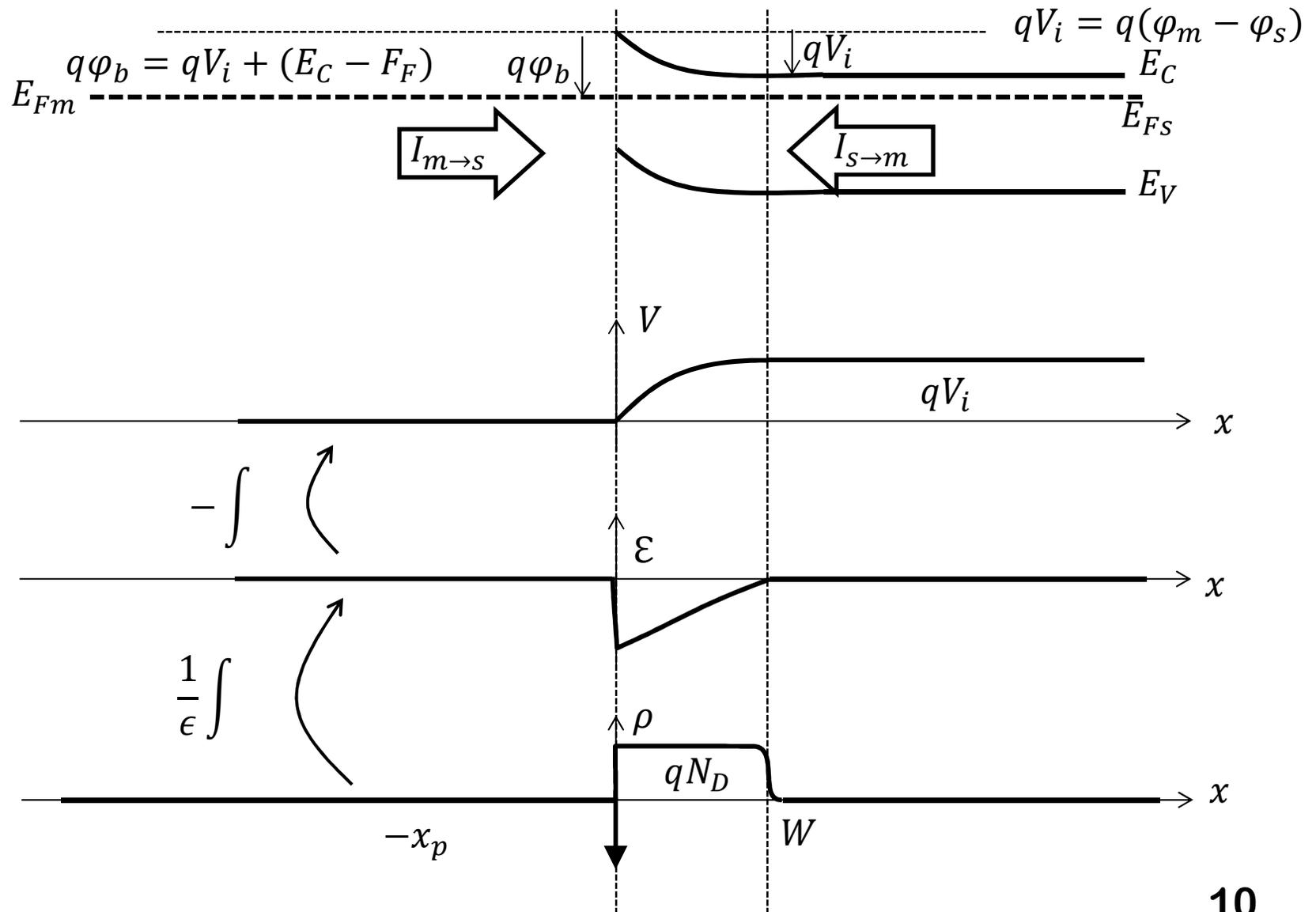
MS junctions – Qualitative

1. 
2. 
3. 
4. 
5. 



MS junctions – Qualitative

1. 
2. 
3. 
4. 
5. 



MS junctions - Schottky Effect

1.	██████████
2.	██████████████
3.	██████████
4.	████
5.	████

$$\mathcal{E}(0) = -qN_D W / \epsilon$$

$$V_i = -\frac{1}{2}W\mathcal{E}(0) = qN_D W^2 / 2\epsilon$$

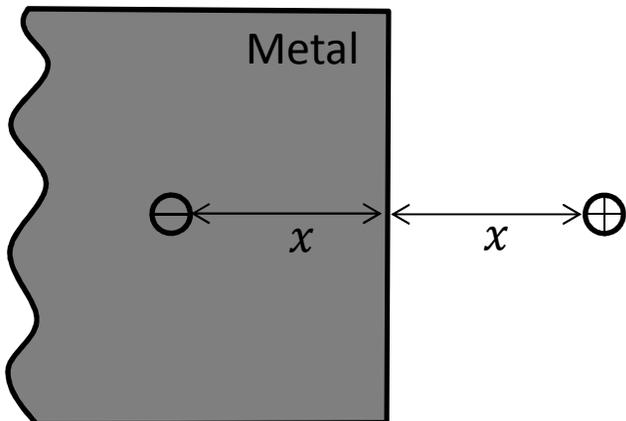
$$W = \sqrt{\frac{2\epsilon}{qN_D} (V_i - V_a)}$$

$$\mathcal{E}(0) = -\sqrt{\frac{2qN_D}{\epsilon} (V_i - V_a)}$$

as $qV_i = q(\varphi_m - \varphi_s)$ seems that V_i is independent of the applied voltage

But it is not! This is known as “Schottky Effect” This will lower $V_i(\varphi_b)$ a little bit.

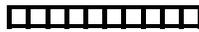
Image method

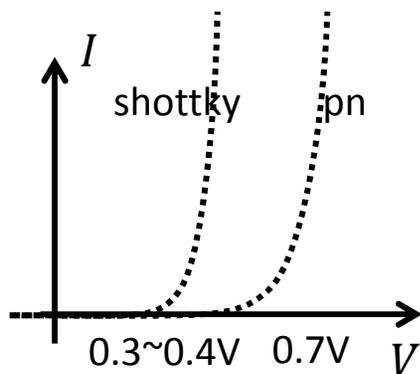
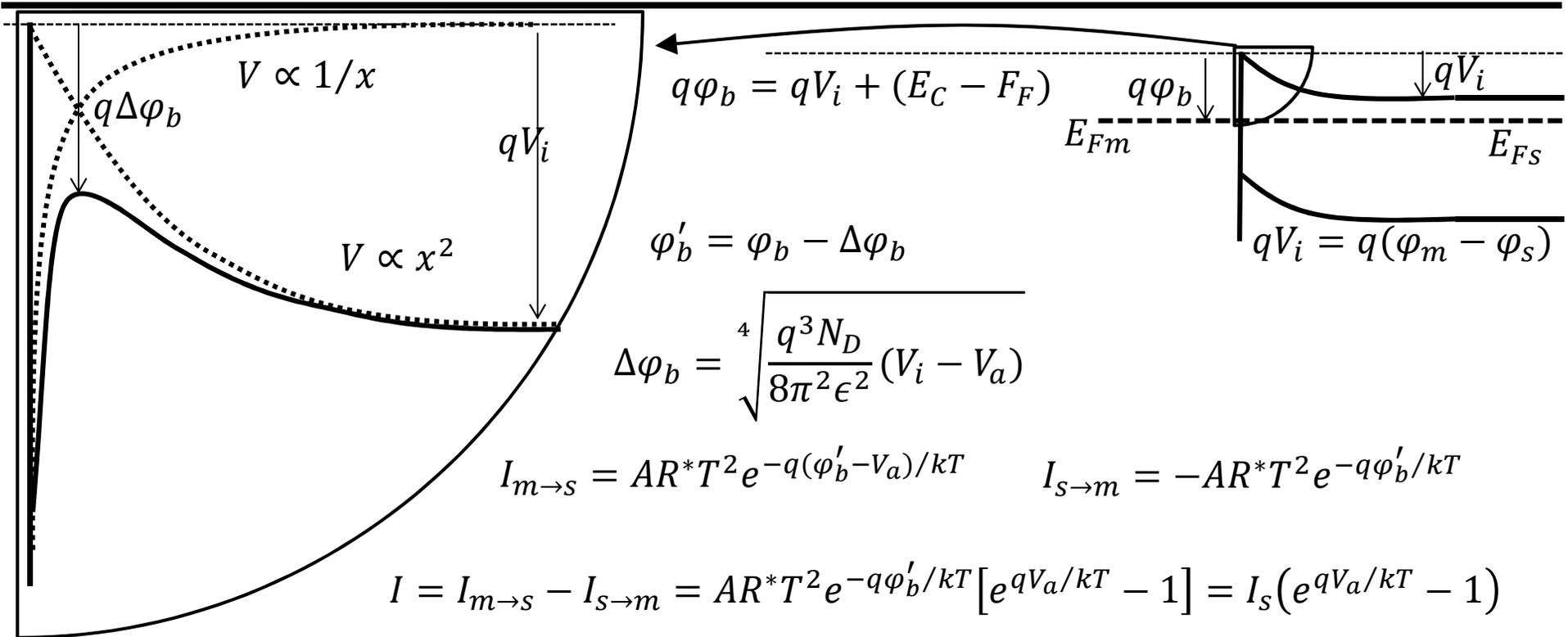


$$F(x) = \frac{-q^2}{16\pi\epsilon x^2}$$

$$\rightarrow \Phi(x) = -qV(x) = \frac{-q^2}{16\pi\epsilon x}$$

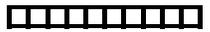
MS junctions, I-V Curve

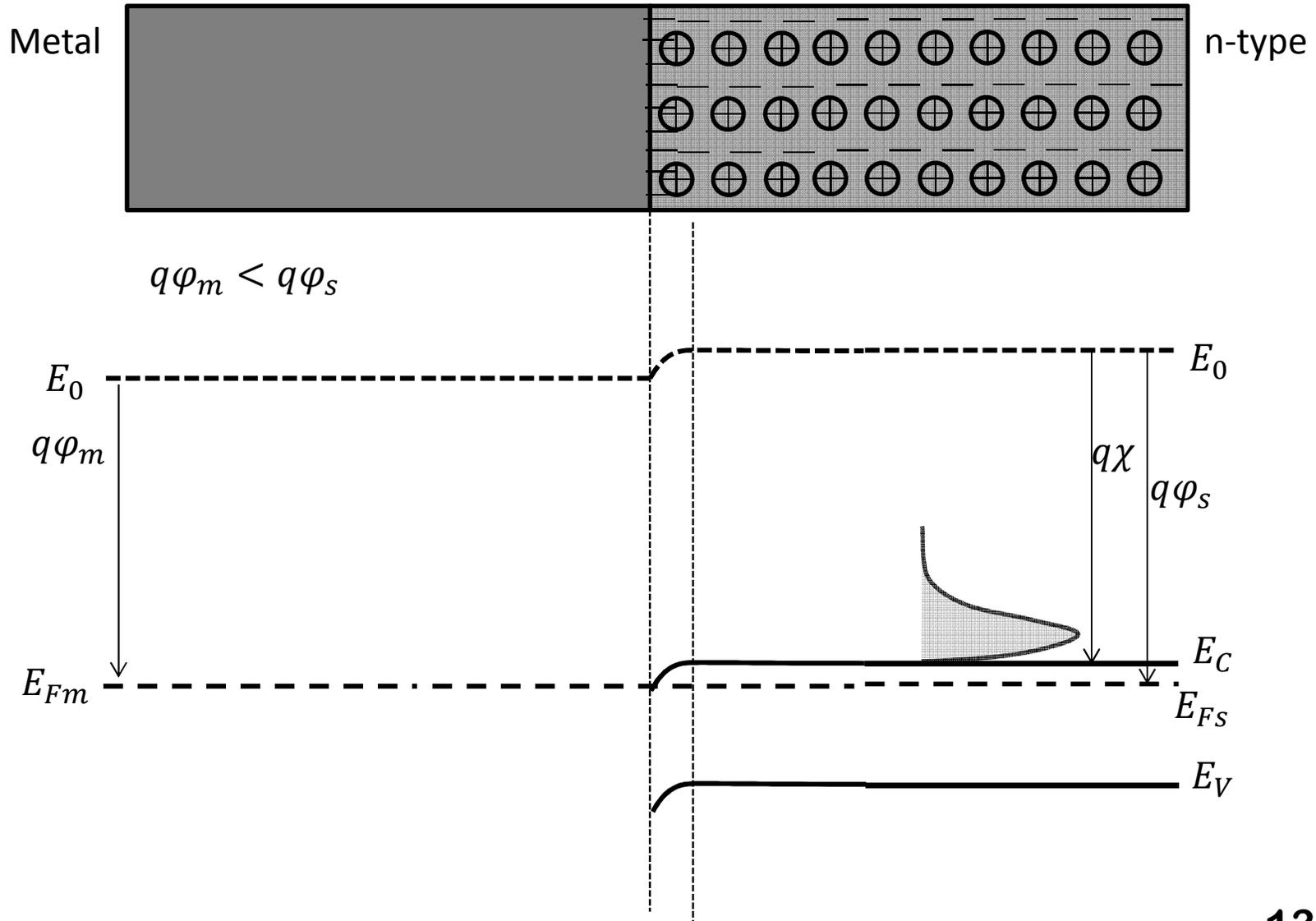
1. 
2. 
3. 
4. 
5. 



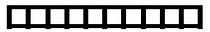
$$I_{s\text{schottky}} \cong 100 - 1000 I_{0pn}$$

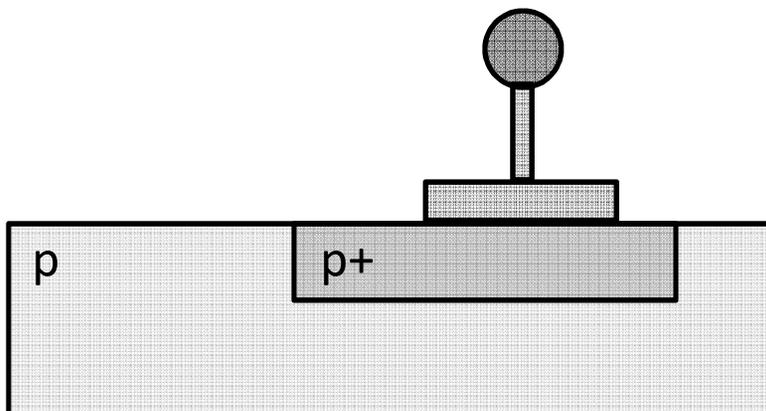
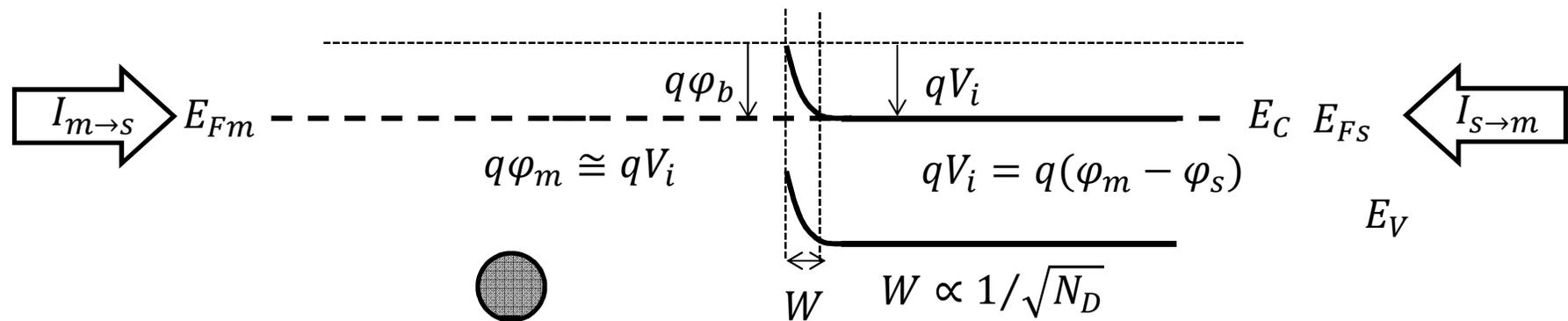
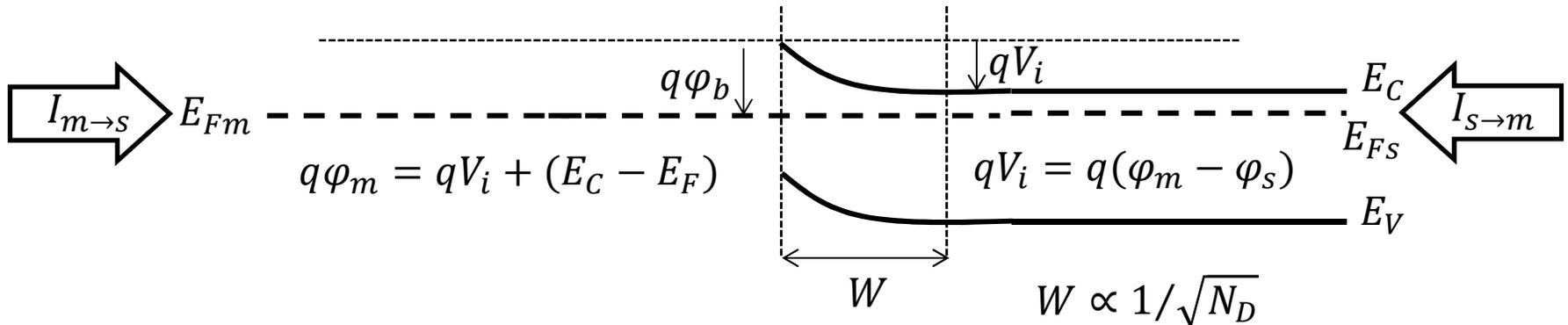
MS junctions – Ohmic Contact

1. 
2. 
3. 
4. 
5. 



MS junctions – Ohmic Contact, Tunneling

1. 
2. 
3. 
4. 
5. 

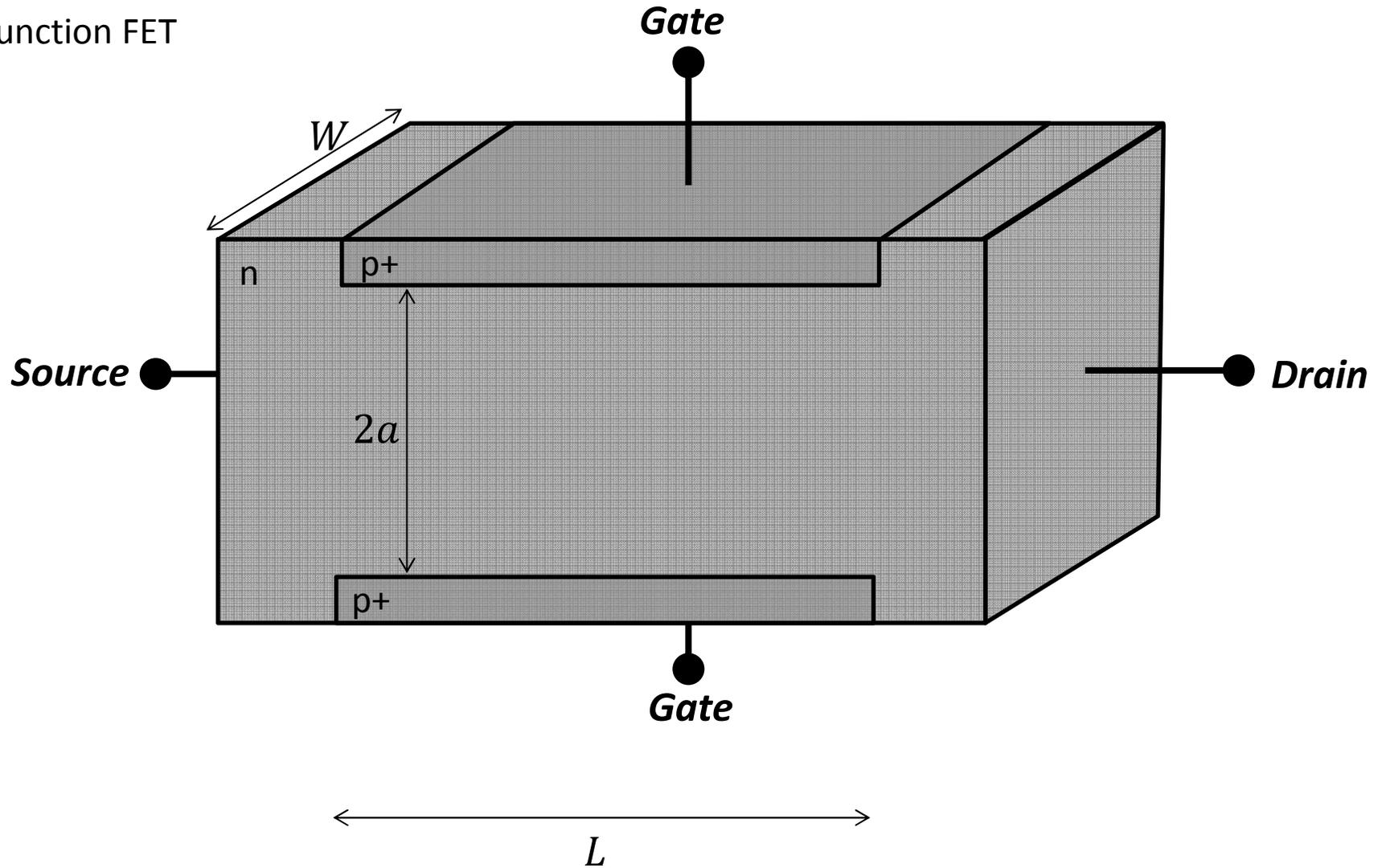


1. 
 2. 
 3. 
 4. 
 5. 
-

JFET (Qualitative)

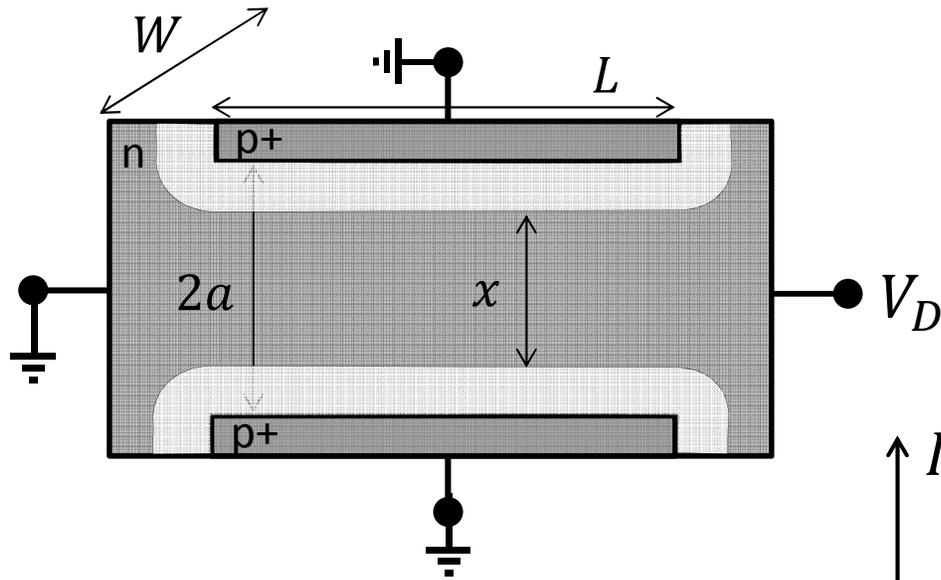
1. 
2. 
3. 
4. 
5. 

Junction FET

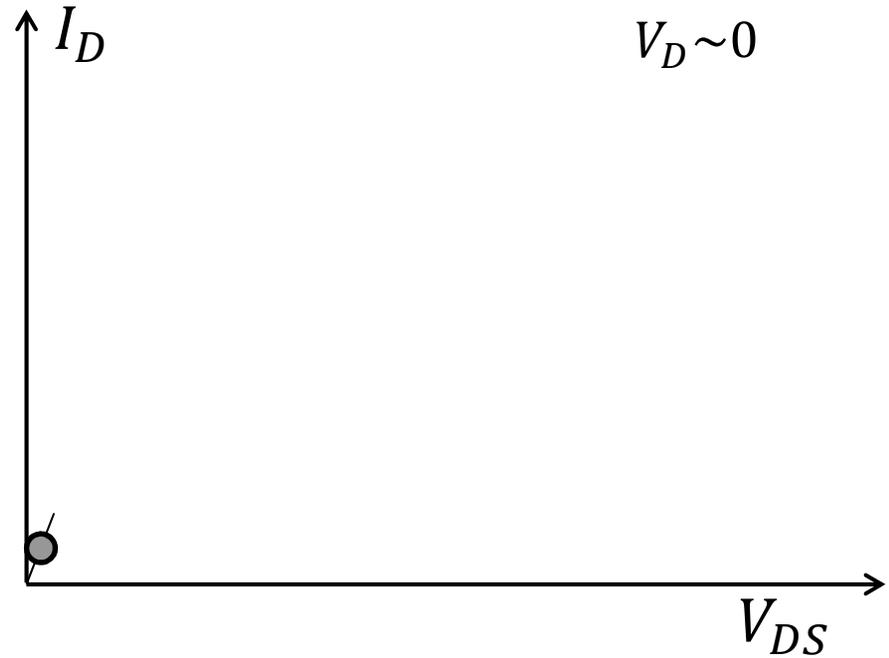


JFET (Qualitative)

1.
2.
3.
4.
5.

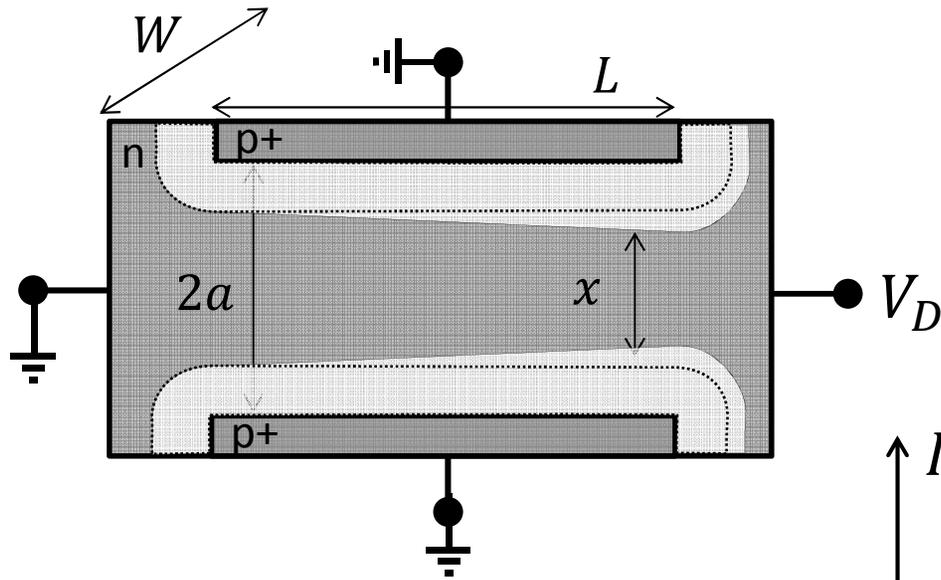


$$R = \rho \frac{L}{Wx}$$

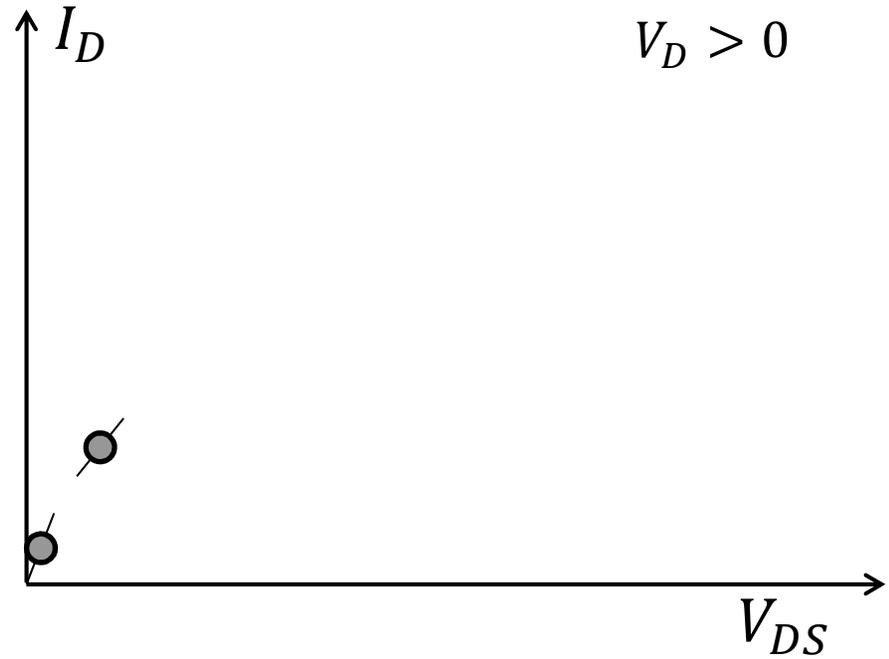


JFET (Qualitative)

1.
2.
3.
4.
5.

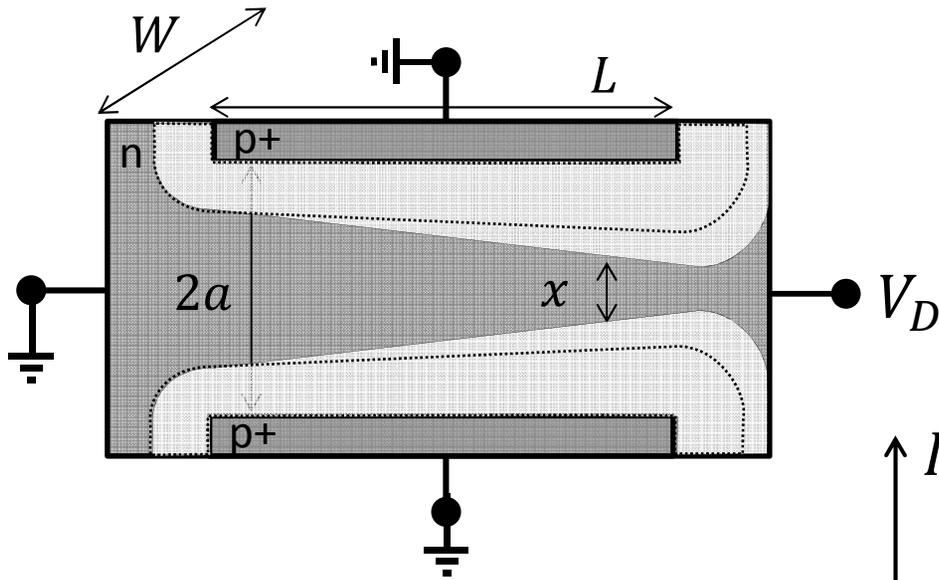


$$R = \rho \frac{L}{Wx}$$

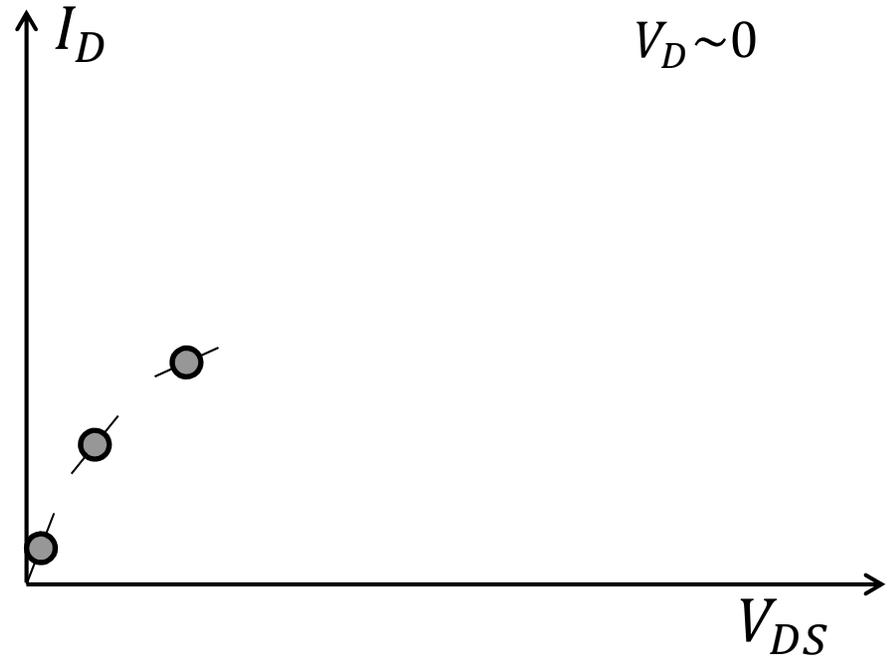


JFET (Qualitative)

1.
2.
3.
4.
5.

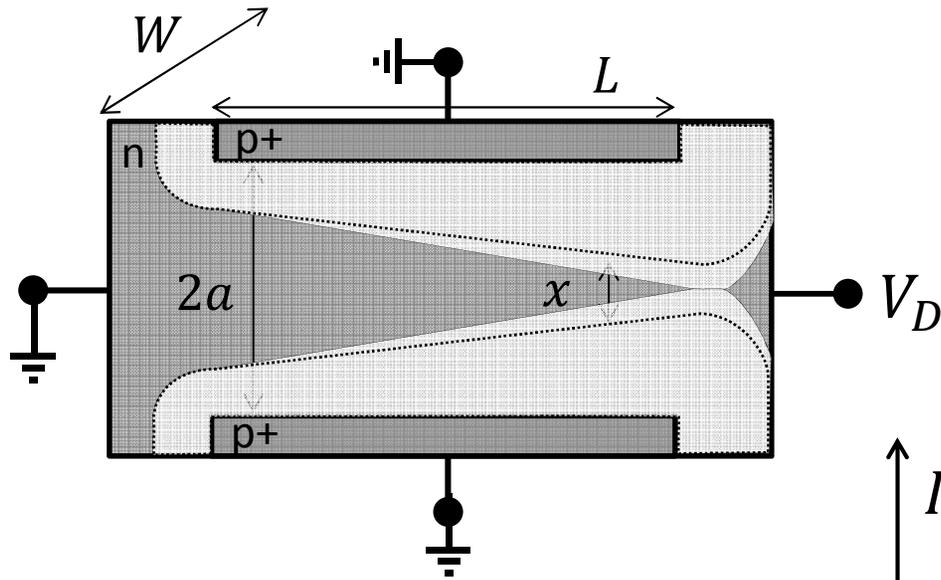


$$R = \rho \frac{L}{Wx}$$

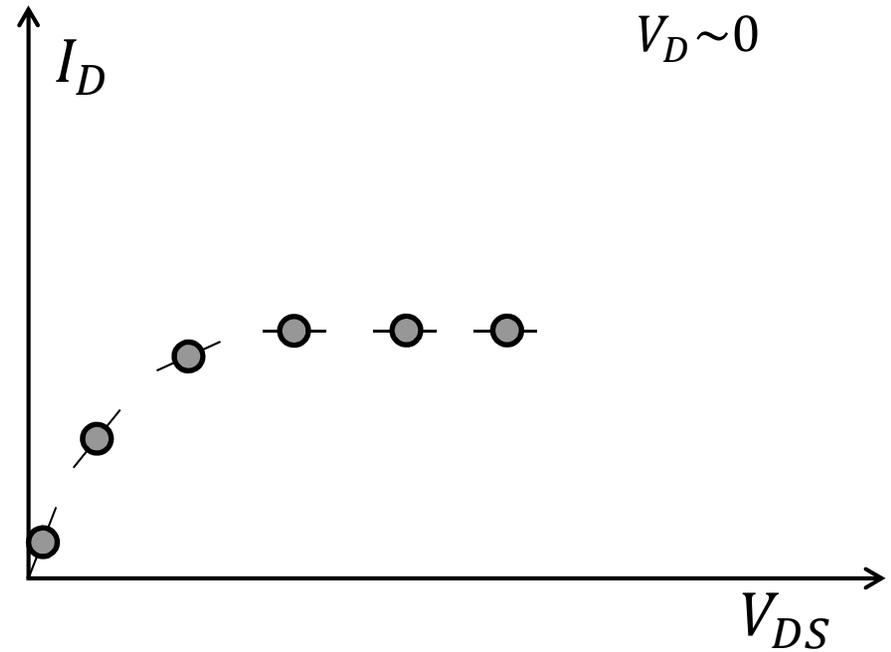


JFET (Qualitative)

1.
2.
3.
4.
5.

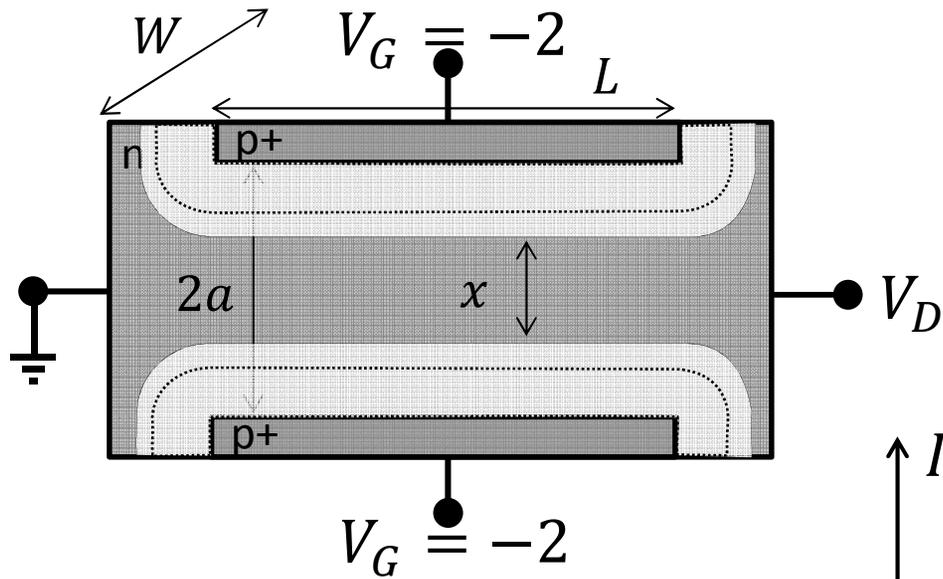


$$R = \rho \frac{L}{Wx}$$

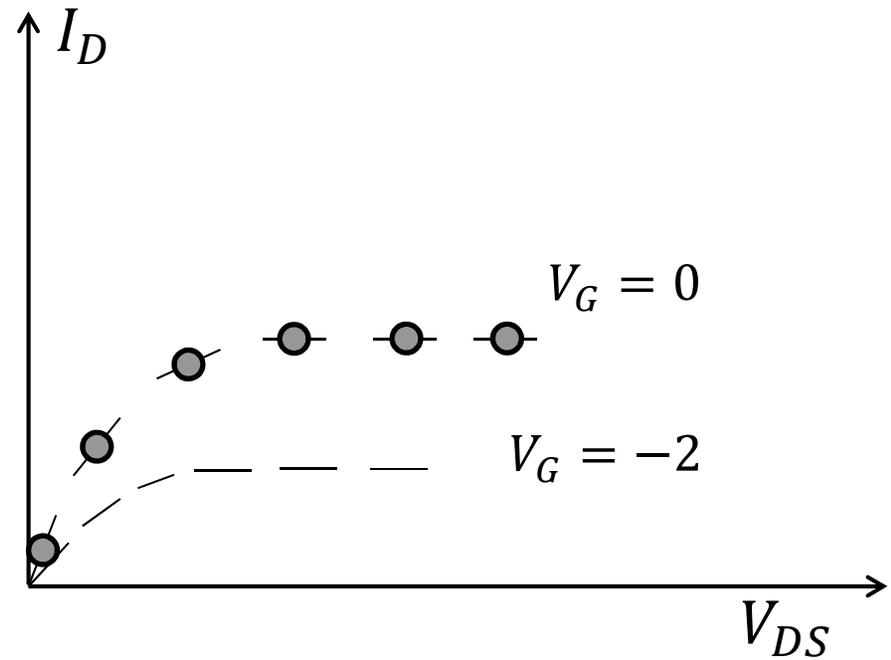


JFET (Qualitative)

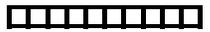
1.
2.
3.
4.
5.

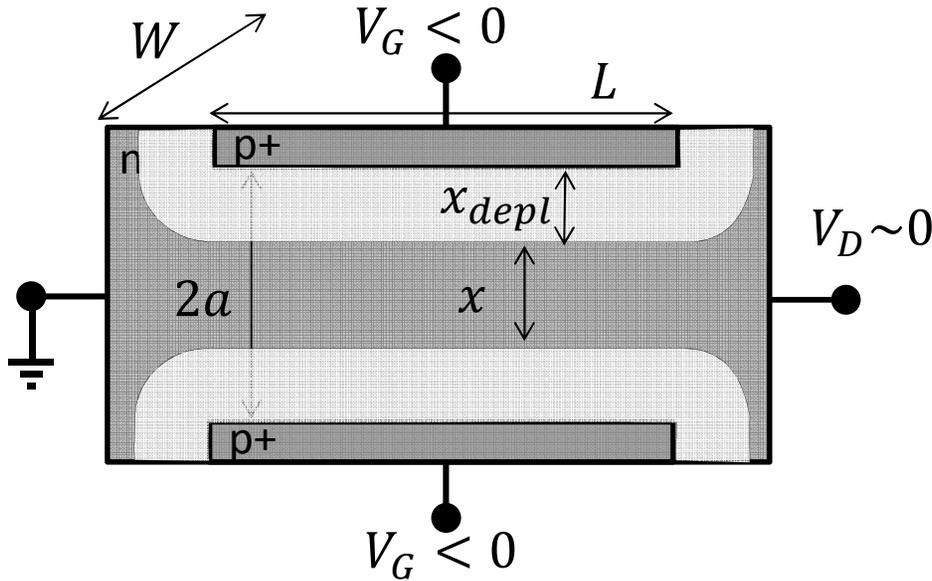


$$R = \rho \frac{L}{Wx}$$



JFET (Qualitative)

1. 
2. 
3. 
4. 
5. 



$$V_G = 0 \rightarrow x_{depl} = \sqrt{\frac{2\epsilon\phi_0}{qN_D}}$$

$$\phi_0 = \frac{kT}{q} \ln \frac{N_A N_D}{n_i^2}$$

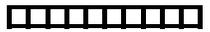
$$\phi_0 = \frac{E_G}{2q} + \frac{kT}{q} \ln \frac{N_D}{n_i}$$

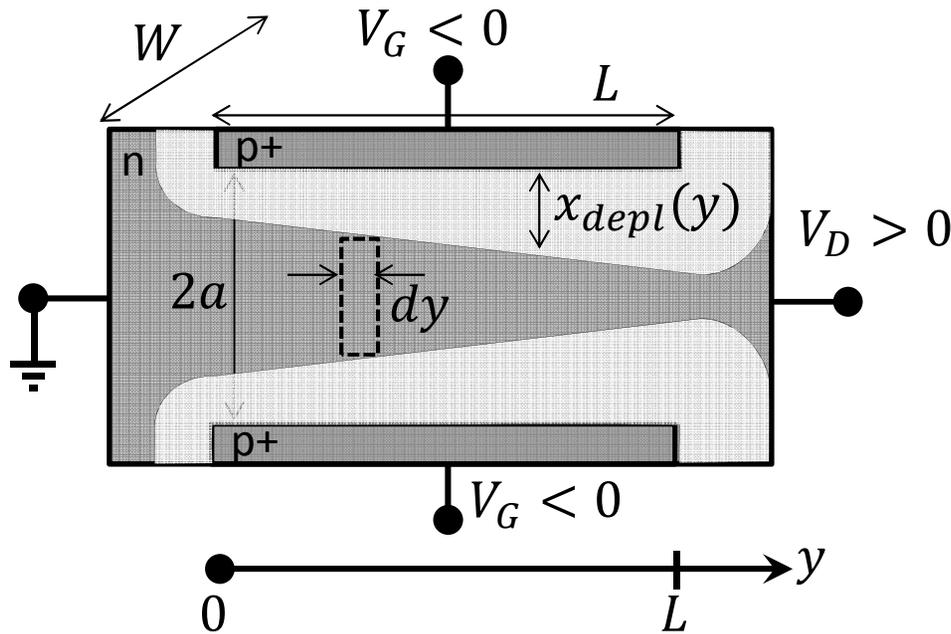
$$x_{depl} = \sqrt{\frac{2\epsilon(\phi_0 - V_G)}{qN_D}}$$

$$\delta I_D = \sigma \frac{A}{L} \delta V_D = q\mu_n N_D \frac{2(a - x_{depl})W}{L} \delta V_D$$

Pinch-off $x_{depl} = a \rightarrow V_p = \phi_0 - \frac{qN_D a^2}{2\epsilon}$

JFET, I-V curve

1. 
2. 
3. 
4. 
5. 



$$x_{depl} = \sqrt{\frac{2\epsilon(\phi_0 - V_G + V(y))}{qN_D}}$$

B.C. $V(0) = 0, \quad V(L) = V_D$

$$dR(y) = \frac{1}{q\mu_n N_D} \frac{dy}{2(a - x_{depl}(y))W}$$

$$dV(y) = I_D dR(y)$$

$$dV(y) = \frac{I_D}{q\mu_n N_D} \frac{dy}{2(a - x_{depl}(y))W}$$

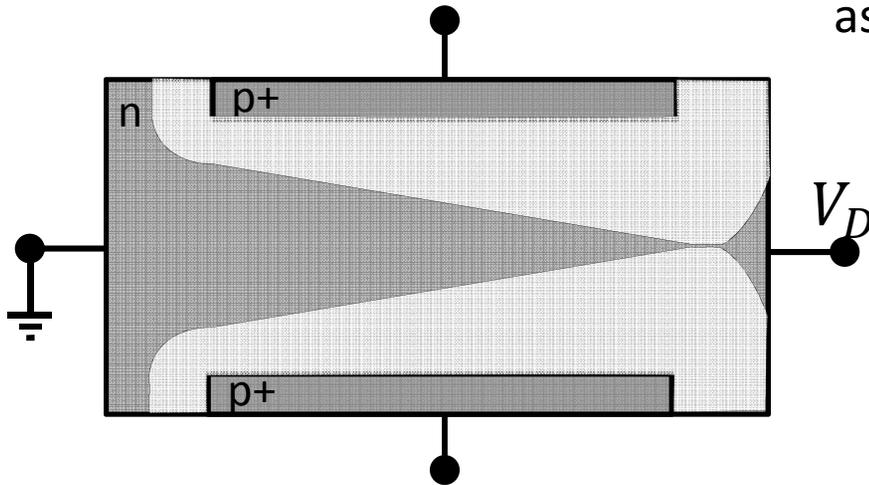
$$q\mu_n N_D \int_0^{V_D} \left[a - \sqrt{\frac{2\epsilon}{qN_D} (\phi_0 - V_G + V(y))} \right] dV = I_D \int_0^L dy = I_D L$$

JFET, I-V curve

1. 
2. 
3. 
4. 
5. 

$$I_D = g_0 \left\{ V_D - \frac{2}{3} \sqrt{\frac{2\epsilon}{qN_D a^2}} \left[(V_D + \varphi_0 - V_G)^{3/2} - (\varphi_0 - V_G)^{3/2} \right] \right\}$$

as: $g_0 = 2q\mu_n N_D a W / L$



$$V_{Dsat} = V_G - V_p = V_G - \varphi_0 - \frac{qN_D a^2}{2\epsilon}$$

$$I_{Dsat} = I_D \Big|_{V_D=V_{Dsat}} = g_0 \left\{ \frac{qN_D a^2}{6\epsilon} - (\varphi_0 - V_G) + \frac{2}{3} \sqrt{\frac{2\epsilon}{qN_D a^2}} (\varphi_0 - V_G)^{3/2} \right\}$$

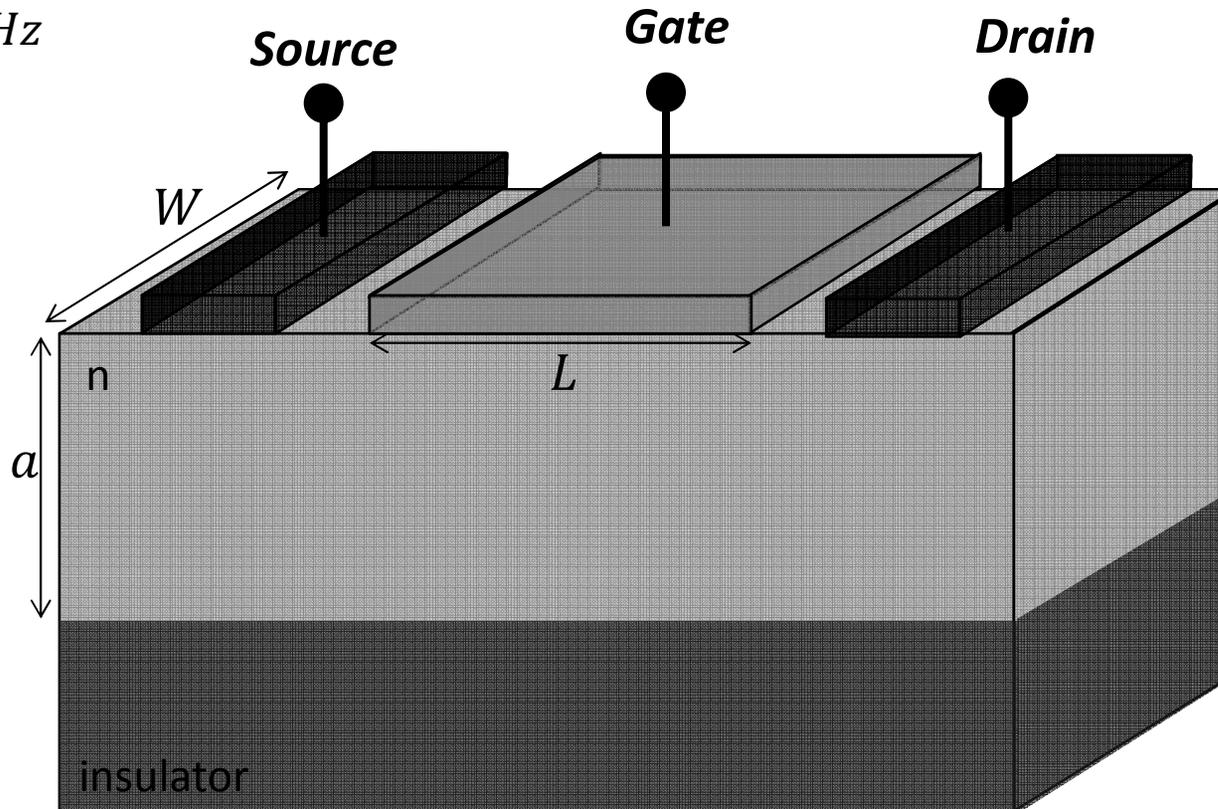
1. 
 2. 
 3. 
 4. 
 5. 
-

MESFET

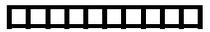
- 1. 
- 2. 
- 3. 
- 4. 
- 5. 

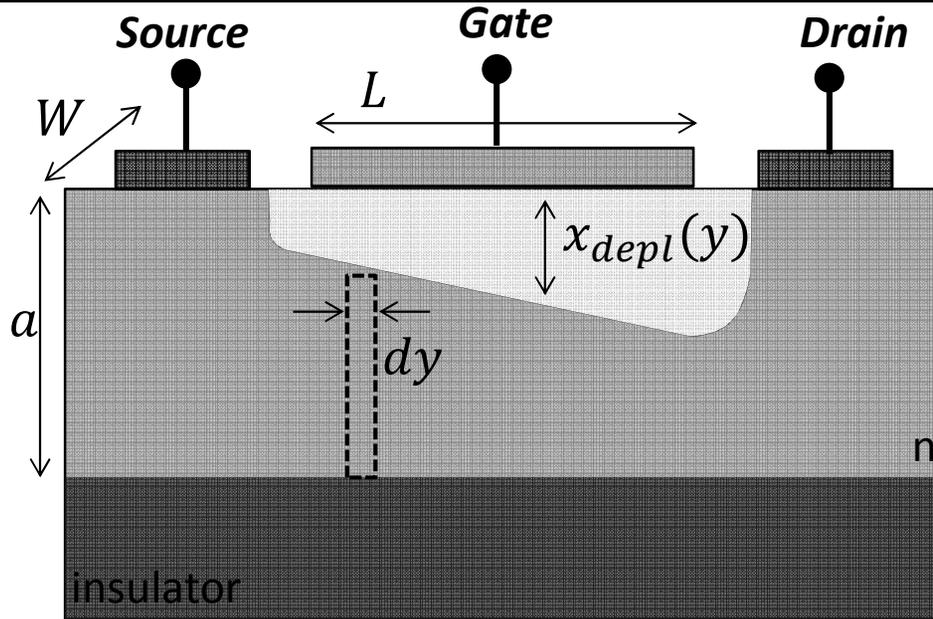
MESFET (metal semiconductor field effect transistor)

$$f_T > 100\text{GHz}$$



MESFET (Qualitative)

1. 
2. 
3. 
4. 
5. 



$$V_D = 0 \rightarrow x_{depl} = \sqrt{\frac{2\epsilon}{qN_D} (V_i - V_G)}$$

$$x_{depl} \Big|_{V_G=V_T} = a$$

$$\rightarrow V_T = V_i - \frac{qN_D a^2}{2\epsilon}$$

$$V_D > 0 \rightarrow x_{depl} = \sqrt{\frac{2\epsilon}{qN_D} (V_i - V_G + V(y))}$$

$$V(0) = 0, V(L) = V_D$$

$$dV = I_D dR =$$

$$= I_D \frac{1}{q\mu_n N_D} \frac{dy}{(a - x_{depl}(y)) W} = \frac{I_D dy}{q\mu_n N_D \left(a - \sqrt{\frac{2\epsilon}{qN_D} (V_i - V_G + V(y))} \right) W}$$

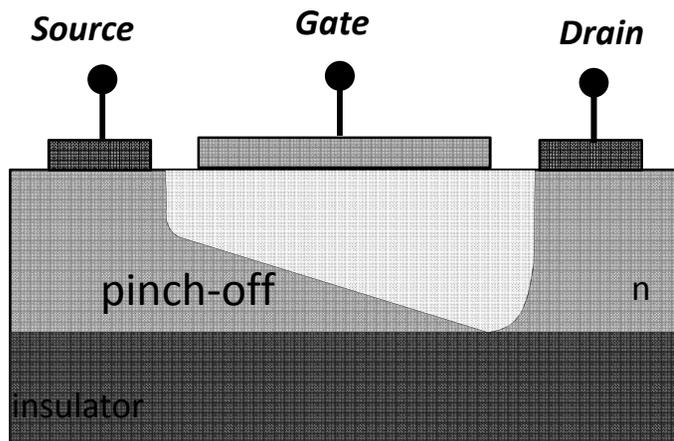
MESFET (Qualitative)

1. 
2. 
3. 
4. 
5. 

$$I_D = g_0 \left\{ V_D - \frac{2}{\sqrt{V_p}} \left[(V_D + V_i - V_G)^{3/2} - (V_i - V_G)^{3/2} \right] \right\}$$

$$g_0 = q\mu_n N_D W / L$$

$$V_p = \frac{qN_D a^2}{2\epsilon}$$



$$V_{D_{sat}} = V_p - V_i + V_G = V_G - V_T$$



$$I_D = g_0 \left\{ \frac{V_p}{3} - \frac{2}{\sqrt{V_p}} (V_i - V_G)^{3/2} - V_i + V_G \right\}$$

$$g_m = \left. \frac{\partial I_D}{\partial V_G} \right|_{V_D} = g_0 \left(1 - \sqrt{\frac{V_i - V_G}{V_p}} \right)$$